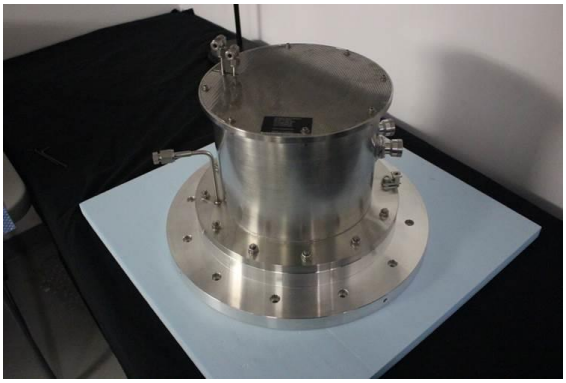
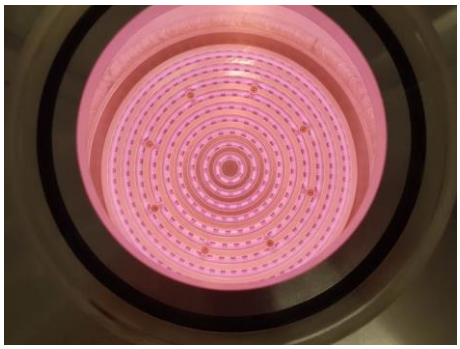
The NEXT GENERATION of EPITAXY

MEAglow

Large Area Plasma Assisted ALD



As well as ICP replacement sources, Meaglow has developed a range of wider area plasma sources



- Conversion of commercial and home built ALD systems.
- 300 and 600 watt systems , higher power on demand, a 3 kilowatt , 12” source is shown to right.
- 4” and 8” wafer diameter, plus larger on request.
- 300 watt systems may not require water cooling
- Oxides, nitrides, other
- **Low oxygen contamination** (no dielectrics)
- Cost effective
- High electron density – similar to or greater than inductively coupled and microwave plasma sources, up to 10^{12} cm^{-3} for some plasma conditions.
- Wide range of operating pressures (eg. from <50 mTorr to >5 Torr).
- Improved growth per cycle for many material systems

Related Papers:

- A. Mohammad, et. al., J. Vac. Sci. Technol. A**37** (2019) 020927.
- C. Ozgit-Akgun, E. Goldenberg, A. Kemal Okyay and N. Biyikili, Journal of Materials Chemisty C **2** (2014) 2123.
- K. S. A. Butcher, V. Georgiev and D. Georgieva, Coatings **11** (2021) 1506.

For more information on Meaglow Ltd or its hollow cathode plasma sources, visit our website www.meaglow.com or contact us at info@meaglow.com .

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